(Following Paper ID and Roll No.			•			
PAPER ID: 1248 Roll No.						

B.Tech.

(SEM. III) ODD SEMESTER THEORY EXAMINATION 2013-14

ELECTRONIC DEVICES

Time: 3 Hours

Total Marks: 100

Note: - Attempt all Sections.

SECTION-A

1. Attempt all parts:

 $(2 \times 10 = 20)$

- (a) What do you mean by Effective Mass? How does it depend on Energy Band?
- (b) Draw and explain Fermi Dirac distribution function.
- (c) What is Punch through in diode?
- (d) What is Contact Potential and how does it vary with the Biasing?
- (e) State difference between Phosphorescence and Fluorescence.
- (f) Explain carrier life time. How direct recombination life time differs from indirect recombination life time?
- (g) Write down the maximum power delivered by solar cell.
- (h) Draw V-I characteristics of Photodiode and what is the significance of 3rd and 4th quadrant operation of Photodiode?

- (i) What is Population Inversion Layer in LASER? Write down the difference between stimulated emission and spontaneous emission.
- (j) How a BJT is used as an amplifier and a switch?

SECTION-B

- 2. Attempt any three parts:
- $(3\times10=30)$
- (a) (i) What is mobility and discuss its dependency on temperature and doping concentration.
 - (ii) Derive the expression for the equilibrium carrier concentration (n₀, p₀) using Fermi Dirac Distribution Function.
- (b) (i) What is Diffusion Length? Derive its value using continuity equation.
 - (ii) Discuss the relationship between Photoconductivity and Mobility of carriers.
- (c) (i) Differentiate between Zener and Avalanche Breakdown.
 - (ii) Derive the expression for electron current in n type material of a forward Biased PN junction.
- (d) (i) Write the special features of MESFET. Differentiate between MOSFET and MESFET.
 - (ii) Differentiate between Rectifying contacts and Non Rectifying contacts with the help of Band Diagram.
- (e) (i) Explain different components of current flow through the structure of a N-P-N transistor with the help of current flow diagram.
 - (ii) What is Photo Detector? Explain the operation of p-i-n photodetector. What are the suitable materials of it? How can it be made more sensitive to low level intensity of light?

SECTION-C

Note: Attempt all questions. $(5\times10=50)$

- 3. Attempt any two parts:
 - (a) Discuss temperature dependency of carrier Concentration.
 - (b) A semiconductor has $\mu_c = 10^{19}/\text{cm}^3$, $\mu_v = 0.5 \times 10^{19}/\text{cm}^3$ and $E_g = 2$ eV. It is doped with $10^{17}/\text{cm}^3$ donors. Calculate e⁻ and hole and intrinsic carrier concentration at 62.7°C. Draw its energy band diagram showing the position of E_p .
 - (c) What is Hall Effect? Derive the expression for Hall Angle.
- 4. Attempt any two parts:
 - (a) What is Quasi Fermi Level ? An n type Si sample with $\mu_d = 10^{15}/\text{cm}^3$ is steadily illuminated such that $g_{op} = 10^{21}$ EHP/cm³-s. If $\tau_n = \tau_p = 1$ µs for this excitation. Calculate the separation in the Quasi Fermi Level $(F_n F_p)$.
 - (b) Write short notes on:
 - (i) Cathodoluminesence
 - (ii) Electroluminesence.
 - (c) What do you mean by diffusion of carriers? Derive expression for Diffusion Current. Draw drift and diffusion of electron and hole in an applied electric field.
- 5. Attempt any two parts:
 - (a) Derive the expression for Penetration depth X_n and X_p in N and P Region respectively for a PN jn diode. Also derive an expression for depletion region width.
 - (b) What is time variation of Stored Charge? Draw and explain the excess hole distribution in n region as a function of time during the transient.

3

- (c) An abrupt Si P-N junction has $\mu_a = 10^{18} \text{cm}^{-3}$ on one side and $\mu = 5 \times 10^{15} \text{cm}^{-3}$ on the other side.
 - (i) Calculate Fermi Level Position at 300 K in P and N Regions.
 - (ii) Draw an equilibrium band diagram for the junction and determine the contact potential V_o from the diagram.

6. Attempt any two parts:

- (a) What is the difference between Homojunction and Heterojunction? Explain Heterojunction with the help of ideal band diagram.
- (b) For a MOSFET. Given that $L_{min} = 0.4 \mu m$, $t_{ox} = 8 nm$, $\mu_n = 450 \text{ cm}^2/\text{V-s}$ and $V_t = 0.7 \text{ V}$. Find out C_{ox} , K'_n . For a MOSFET with W/L = 8 $\mu m/0.8 \mu m$, calculate the value of V_{GS} and V_{DSmin} needed to operate a transistor in saturation region with a DC current $I_D = 100 \mu A$.
- (c) Explain the operation of enhancement type MOSFET and discuss its Drain and Transfer characteristics.

7. Attempt any two parts:

- (a) Explain Ebers-Moll Model of BJT.
- (b) Write a short note on semiconductor LASER.
- (c) What is Base Width Modulation and Early effect in BJT?